

EUROPEAN PATENT OFFICE

Patent Abstracts of Japan

PUBLICATION NUMBER : 06224171
PUBLICATION DATE : 12-08-94

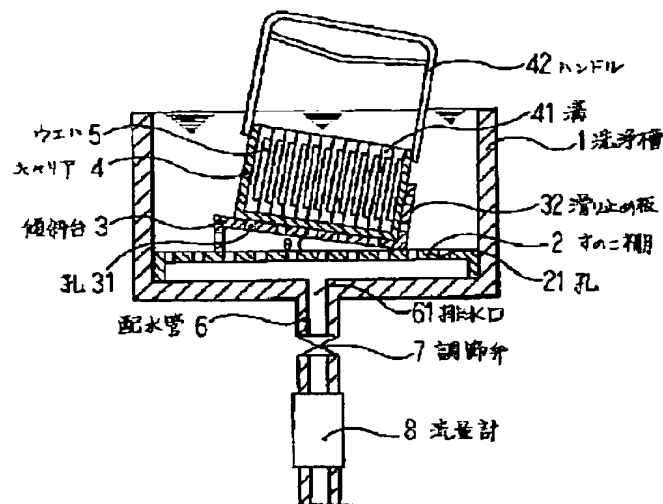
APPLICATION DATE : 25-01-93
APPLICATION NUMBER : 05045641

APPLICANT : KOMATSU ELECTRON METALS CO LTD;

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INT.CL. : H01L 21/304 B08B 11/04

TITLE : WAFER CLEANING METHOD AND DEVICE



ABSTRACT : PURPOSE: To drain off water evenly from a wafer after it is cleansed so as to make a natural oxide film uniform in thickness.

CONSTITUTION: A tilted pad 3 is placed on a drain-board 2 provided inside a cleansing tank 1, and a carrier 4 loaded with wafers 5 is placed on the tilted pad 3. After the wafers 5 are etched and cleansed as kept in the above state water is drained off at a constant speed through a distributing pipe 6 provided to the base of the cleansing tank 1. A drainage control valve 7 and a flowmeter 8 are provided to the distributing pipe 6 so as to strictly control water in drain speed. It is preferable that a drain speed is set smaller than 1000mm/minute wherein a water film is continuously and uniformly formed with a descent of water surface on the surface of the wafer 5 where a CVD film is formed.

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